In the Claims:

1. (Currently amended) A semiconductor laser device comprising:

an optically pumped surface-emitting vertical emitter region [[(2)]] which has an active radiation-emitting vertical emitter layer; [[(3)]] and

at least one monolithically integrated pump radiation source [[(5)]] for optically pumping the vertical emitter [[(2)]], which has an active radiation-emitting pump layer [[(6)]], characterized in that wherein the pump layer [[(6)]] follows the vertical emitter layer [[(3)]] in the vertical direction; [[,]]

a conductive layer (13) is provided between the vertical emitter layer [[(3)]] and the pump layer; and [[(6),]]

a contact (9) is applied on the side of the semiconductor layer device which is closer to the pump layer [[(6)]] than to the conductive layer; (13), and

whereby an electrical field can be applied between the conductive layer [[(13)]] and the contact [[(9)]] for generating pump radiation [[(7)]] by charge carrier injection.

- 2. (Currently amended) The semiconductor laser device as claimed in claim 1, characterized in that wherein the semiconductor laser device is partially ablated so that the conductive layer (13) is partially exposed.
- 3. (Currently amended) The semiconductor laser device as claimed in claim 2, characterized in that wherein the semiconductor laser device is ablated in the form of parallel trenches (22).

- 4. (Currently amended) The semiconductor laser device as claimed in claim 2 or 3, characterized in that, wherein a further contact [[(15)]] is applied to the exposed areas of the conductive layer [[(13)]].
- 5. (Currently amended) The semiconductor laser device as claimed in claim 4, characterized in that wherein a layer [[(14)]] which is conductive and which is transparent for radiation of a wavelength as generated by the vertical emitter region (2) is pump radiation source provided between a conductive layer [[(13)]] and the further contact [[(15)]].
- 6. (Currently amended) The semiconductor laser device as claimed in <u>claim 2</u>, wherein one of claims 2 to 5, characterized in that, an etch stop layer [[(17)]] which is resistant to an etching process which is suitable for exposing the conductive layer [[(13)]] is provided adjacently to the conductive layer [[(13)]].
- 7. (Currently amended) The semiconductor laser device as claimed in <u>claim 1</u>, wherein one of claims 1 to 6, characterized in that the conductive layer [[(13)]] is arranged vertically in such a manner that it is located in a node of the radiation field in the resonator of the vertical emitter region [[(2)]].
- 8. (Currently amended) The semiconductor laser device as claimed in <u>claim 1</u>, <u>wherein one of claims 1 to 7</u>, characterized in that a vertical waveguide structure [[(16)]] is provided between the vertical emitter layer [[(3)]] and the conductive layer [[(13)]].

- 9. (Currently amended) The semiconductor laser device as claimed in claim 8, characterized in that wherein the vertical waveguide structure [[(16)]] has other optical characteristics in the region in which it is located between the contact [[(9)]] and the further contact [[(15)]], seen laterally, than in the region in which it is not located between the contact [[(9)]] and the further contact [[(15)]].
- 10. (Currently amended) The semiconductor laser device as claimed in claim 9, characterized in that wherein[[,]] the vertical waveguide structure [[(16)]] is oxidized in the region in which it is located between the contact [[(9)]] and the further contact [[(15)]], seen laterally.
- 11. (Currently amended) The semiconductor laser device as claimed in <u>claim 1</u>, wherein one of claims 1 to 10, characterized in that the pump layer [[(6)]] and the vertical emitter layer [[(3)]] are followed in the vertical direction by an internal cavity reflective structure.
- 12. (Currently amended) The semiconductor laser device as claimed in claim 11, characterized in that wherein the internal cavity reflective structure is a Bragg reflector structure [[(10)]].
- 13. (Currently amended) The semiconductor laser device as claimed in <u>claim 11</u>, <u>wherein one of claims 11 or 12</u>, <u>characterized in that</u> the internal cavity reflective structure is arranged between the vertical emitter layer [[(3)]] and a substrate [[(8)]] and the radiation generated by the vertical emitter layer [[(3)]] is launched on the side opposite the substrate.

- 14. (Currently amended) The semiconductor laser device as claimed in claim 1, wherein one of claims 1 to 13, characterized in that the vertical emitter layer [[(3)]] is associated with an external resonator reflector [[(19)]] which, together with the internal cavity reflective structure, forms the resonator for the vertical emitter region [[(2)]].
- 15. (Currently amended) The semiconductor laser device as claimed in claim 14, characterized in that wherein beam-shaping elements are arranged in the resonator.
- 16. (Currently amended) The semiconductor laser device as claimed in <u>claim 14</u>, wherein one of claims 14 or 15, characterized in that frequency-selective elements are arranged in the resonator.
- 17. (Currently amended) The semiconductor laser device as claimed in <u>claim 14</u>, wherein one of claims 14 to 16, characterized in that frequency-converting elements are arranged in the resonator.
- 18. (Currently amended) The semiconductor laser device as claimed in <u>claim 1</u>, wherein one of claims 1 to 17, characterized in that the vertical emitter layer [[(3)]] and/or the pump layer [[(6)]] in each case have one or more quantum well structures.

19. (Currently amended) The semiconductor laser device as claimed in claim 18, wherein 14, characterized in that the quantum well structures can contain quantum troughs, quantum wires, quantum dots and any combination of these structures.